BUNDESREPUBLIK DEUTSCHLAND



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Ausstellungspriorität:	
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Land: Aktenzeichen:	
Bezeichnung:	Einzelplatte für Stabfußboden
Zusatz zu:	_
Ausscheidung aus:	
Anmelder:	Weber geb. Walter, Gisela, 7000 Stuttgart
Vertreter:	
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	Ausstellungspriorität: Unionspriorität Datum: Land: Aktenzeichen: Bezeichnung: Zusatz zu: Ausscheidung aus: Anmelder: Vertreter:

Attorney Docket No.: MUH-12807

Appl. No. 10/680,379 Amdt. dated 5/9/07 Reply to Office action of 1/16/07

the organic compound; and

providing light-opaque regions opaque to the activation radiation used for the exposure in

during the exposure, obtaining unexposed sections in the organic compound, the unexposed sections being disposed behind the light-opaque regions as seen in a direction of a radiation source used for the exposure to the organic compound.

Claim 7 (original). The method according to claim 6, which further comprises forming the light-opaque regions by a gate electrode.

Claim 8 (original). The method according to claim 6, which further comprises forming the light-opaque regions utilizing a gate electrode.

Claim 9 (currently amended). A method for fabricating an organic field-effect transistor, which comprises:

depositing a gate electrode, a source contact, a drain contact, a gate dielectric, and an electrically conductive organic semiconductor <u>arranged between the source contact and drain contact</u> on a substrate;

introducing a doping substance activated by exposure with an activation radiation into the organic semiconductor;

carrying out section-by-section exposure with the activation radiation;

after the exposure, removing unbounded doping substance from the organic semiconductor to irreversibly fix, in regions of the organic semiconductor adjoining the source contact and the drain contact, the doping substance in the organic semiconductor and to obtain contact regions adjoining the source contact and the drain contact, the contact regions having increased electrical conductivity, wherein a first distance is retained between the gate dielectric and the source contact and a second distance is retained between the gate

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dielectric and the drain contact, at which the organic semiconductor is applied directly with the contact region to the substrate; and

restoring original electrical conductivity in unexposed regions.

Claim 10 (original). The method according to claim 9, which further comprises applying a photomask for the section-by-section exposure.

Claim 11 (original). The method according to claim 9, which further comprises carrying out the section-by-section exposure by applying a photomask.

Claim 12 (original). The method according to claim 9, which further comprises:

providing the substrate as a substrate transparent to the activation radiation;

carrying out the depositing step by depositing, on the substrate, the source and drain contacts spaced apart from the gate electrode;

depositing a gate dielectric on the gate electrode to obtain a spacing in which the substrate is uncovered between the gate dielectric and the source contact and also between the gate dielectric and the drain contact;

depositing the organic semiconductor on the substrate, the source contact, the drain contact, and the gate dielectric to fill, with the organic semiconductor, at least one of the spacing between the gate dielectric and the source contact and the spacing between the gate dielectric and the drain contact;

carrying out the exposure step with the activation radiation from a side of the substrate to obtain, adjoining the source contact and the drain contact, contact regions having increased conductivity in the organic semiconductor; and

subsequently removing excess doping substance from the organic semiconductor.

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Claim 13 (original). The method according to claim 9, which further comprises simultaneously depositing the gate electrode, the source contact, and the drain contact on the substrate.

Claim 14 (original). The method according to claim 9, which further comprises constructing the gate dielectric from a material transparent to the activation radiation.

Claim 15 (original). The method according to claim 9, which further comprises providing the gate dielectric with a material transparent to the activation radiation.

Claim 16 (withdrawn). An organic field-effect transistor, comprising:

a gate electrode;

a gate dielectric insulating said gate electrode;

a source contact;

a drain contact; and

an organic semiconductor:

being disposed between said source contact and said drain contact;

adjoining at least one of said source contact and said drain contact;

having a contact region with increased electrical conductivity; and

being doped with a doping substance irreversibly fixed in said organic semiconductor.

Claim 17 (withdrawn). The organic field-effect transistor according to claim 16, further comprising:

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a front side; and

a rear side having at least one section formed by said organic semiconductor.

Claim 18 (withdrawn). The organic field-effect transistor according to claim 16, further comprising:

a front side; and

a rear side having said contact region formed by said organic semiconductor.

Claim 19 (withdrawn). The organic field-effect transistor according to claim 17, wherein said rear side includes at least one section formed by one of said source contact and said drain contact, said at least one section adjoining said at least one section formed by said organic semiconductor.

Claim 20 (withdrawn). The organic field-effect transistor according to claim 17, wherein said at least one section formed by said organic semiconductor is doped with said irreversibly fixed doping substance.

Claim 21 (withdrawn). The organic field-effect transistor according to claim 16, wherein said doping substance is irreversibly fixed in said organic semiconductor by a covalent or a coordinate bond.

Claim 22 (withdrawn). The organic field-effect transistor according to claim 16, wherein said doping substance has a covalent or a coordinate bond irreversibly fixing said doping substance in said organic semiconductor.

Claim 23 (withdrawn). The organic field-effect transistor according to claim 16, wherein, in a plan view of the organic field-effect transistor, said gate electrode, said source contact, and said drain contact have no overlap and sections of said organic semiconductor doped with said irreversibly fixed doping substance and having an increased electrical conductivity

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are disposed at least one of between said gate electrode and said source contact and between said gate electrode and said drain contact.

Claim 24 (withdrawn). The organic field-effect transistor according to claim 16, wherein:

in a plan view of the organic field-effect transistor, said gate electrode, said source contact, and said drain contact have no overlap; and

sections of said organic semiconductor doped with said irreversibly fixed doping substance and having an increased electrical conductivity are disposed at least one of between said gate electrode and said source contact and between said gate electrode and said drain contact.